Krzysztof Rola

Lista publikacji

z dnia 31 października 2014

Publikacje w czasopismach

1. Rola K., Ptasiński K., Zakrzewski A., Zubel I., 2014, S***ilicon 45° micromirrors fabricated by etching in alkaline solutions with organic additives***, *Microsystem Technologies* 20: s. 221–226
2. Rola K., Zubel I., 2013, ***Triton surfactant as an additive to KOH silicon etchant***, *Journal of Microelectromechanical Systems* 22: s. 1373–1382
3. Rola K., Zubel I., 2013, ***Application of Triton X-100 surfactant for silicon anisotropic etching in KOH-based solutions***, *Materials Science-Poland* 31: s. 525–530
4. Rola K., Zubel I., 2013, ***Impact of alcohol additives concentration on etch rate and surface morphology of (100) and (110) Si substrates etched in KOH solutions***, *Microsystem Technologies* 19: s. 635-643
5. Zubel I., Kramkowska M., Rola K., 2012, ***Silicon anisotropic etching in TMAH solutions containing alcohol and surfactant additives***, *Sensors and Actuators A: Physical* 178: s. 126-135
6. Zubel I., Granek F., Rola K., Banaszczyk K., 2012, ***Texturization of Si(1 0 0) substrates using tensioactive compounds***, *Applied Surface Science* 258: s. 9067-9072
7. Zubel I., Granek F., Rola K., Banaszczyk K., 2012, ***Zastosowanie związków powierzchniowo czynnych do teksturyzacji podłoży krzemowych***, *Elektronika - konstrukcje, technologie, zastosowania* 2: 9-12
8. Rola K., Zubel I., 2011, ***Investigation of Si(hkl) surfaces etched in KOH solutions saturated with tertiary-butyl alcohol***, *Journal of Micromechanics and Microengineering* 21: nr art. 115026
9. Zubel I., Rola K., Kramkowska M., 2011, ***The effect of isopropyl alcohol concentration on the etching process of Si-substrates in KOH solutions***, *Sensors and Actuators A: Physical* 171: s. 436-445
10. Rola K., Zubel I., 2011, ***Modifying of etching anisotropy of silicon substrates by surface active agents,*** *Central European Journal of Physics* 9: s. 410-416
11. Rola K., Zubel I., 2011, ***Study on etching anisotropy of Si(hkl) planes in solutions with different KOH and isopropyl alcohol concentrations***, *Materials Science-Poland* 29: s. 278-284
12. Zubel I., Rola K., 2011, ***Micromirrors inclined at 45° towards Si substrates fabricated by anisotropic etching***, *Optica Applicata* 41: s. 423-430
13. Rola K., Zubel I., M. Kramkowska, 2011, ***Etching of Si(100) and (110) substrates in KOH solutions saturated and non-saturated with isopropyl alcohol***, *Elektronika - konstrukcje, technologie, zastosowania* 3: s. 50-53

Prace pokonferencyjne

14. Allaf K., Król D., Wymysłowski A., Zubel I., Rola K., 2014, ***Adhesion work analysis by molecular modelling and wetting angle measurement***, *Proceedings of 15th International Conference on Thermal, Mechanical and Multi-Physics Simulation and Experiments in Microelectronics and Microsystems, EuroSimE 2014*, Gent, Belgia

15. Rola K., Zubel I., 2013, ***Anisotropic etching of silicon in potassium hydroxide solutions containing long-chain alcohols***, *Proceedings of 2013 International Students and Young Scientists Workshop "Photonics and Microsystems"*, St. Marienthal, Niemcy, s. 89–93

16. Król D., Wymysłowski A., Zubel I., Rola K., 2013, ***Comparison of the surface energy obtained by using the molecular modelling with the wetting angle measurement***, *Proceedings of 37th International Microelectronics and Packaging IMAPS-CPMT Poland Conference*, Kraków

17. Rola K., Zubel I., 2013, ***Application of Triton surfactant adsorption on Si surface for fabrication of 45° micromirrors***, *Proceedings of SPIE, 11th Conference on Electron Technology, ELTE 2013*; Ryn; vol. 8902, art. no. 89021Y
18. Zubel I., Rola K., Zalewska J., 2013, ***Behavior of tensioactive compounds in the solutions for silicon anisotropic etching***, *Proceedings of SPIE, 11th Conference on Electron Technology, ELTE 2013*; Ryn; vol. 8902, art. no. 89022I

19. Król D., Wymysłowski A., Zubel I., Rola K., 2013, ***Application of molecular modelling for analysis of a surface energy and its comparison with the experimental results based on wetting angle measurement***, *Proceedings of 14th International Conference on Thermal, Mechanical and Multi-Physics Simulation and Experiments in Microelectronics and Microsystems, EuroSimE 2013*, Wrocław

20. Rola K., Ptasiński K., Zakrzewski A., Zubel I., 2012, ***Characterization of 45º micromirrors fabricated by silicon anisotropic etching in solutions containing different organic additives***, *Proceedings of 26th European Conference on Solid-State Transducers, EUROSENSORS 2012, Procedia Engineering* 47: s. 510-513

21. Rola K., Zubel I., 2011, ***Influence of KOH and Alcohol Concentrations on Etching Anisotropy of Si(hkl) Planes***, *Official Proceedings of Microtherm 2011*, Łódź, s. 347-352

22. Rola K., Zubel I., 2011, ***Micromirrors Fabricated by Silicon Anisotropic Etching in KOH Solutions Saturated with Alcohols***, *Proceedings of 2011 International Students and Young Scientists Workshop "Photonics and Microsystems"*, Cottbus, Niemcy

23. Rola K., 2010, ***Silicon Anisotropic Etching In Alkaline Solutions Using (hkl) Planes For MEMS Applications***, *8th Students' Science Conference, Szklarska Poręba*

24. Zubel I. Rola K., 2010, ***Microfabrication of smooth micromirrors inclined at 45º towards Si substrate***, *Proceedings of 10th Electron Technology Conference ELTE 2010 and 34th International Microelectronics and Packaging IMAPS-CPMT Poland Conference*, Wrocław

25. Rola K., Zubel I., Kramkowska M., 2010, ***Model of etching of Si(hkl) substrates in KOH solutions saturated and non-saturated with isopropyl alcohol***, *Proceedings of 10th Electron Technology Conference ELTE 2010 and 34th International Microelectronics and Packaging IMAPS-CPMT Poland Conference*, Wrocław